

## Rib waveguides based on the sol-gel derived $\text{SiO}_2:\text{TiO}_2$ films

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**Abstract**— This work presents rib waveguides fabricated by chemical etching of inorganic two-component  $\text{SiO}_2:\text{TiO}_2$  films. Silica-titania films were fabricated using sol-gel method. In all technological processes involving masking, standard photolithographic procedures were used. A photoresist was used as a mask in the chemical etching processes. Rib waveguides of 5 nm rib height and rib width of less than  $4\mu\text{m}$  were single mode for a wavelength of  $\lambda=635\text{nm}$ . The attenuation determined for fabricated rib waveguides approximately equal to 1,5dB/cm.

Rib waveguides are essential components of integrated optical planar systems for signal processing and for optical sensors. The present work concerns the fabrication technology of rib waveguides developed by our research group [1], [2]. This technology is based on two-component  $\text{SiO}_2:\text{TiO}_2$  optical waveguide films fabricated with a sol-gel method. The fabricated waveguide films are characterized by high refractive index ( $\sim 1.8$ ) and low attenuation ( $\sim 0.3$  dB/m).

The diagram of a rib waveguide is shown on Fig.1. The optical and geometrical parameters describing a rib waveguide are: a refractive index of waveguide film  $n_f$ , substrate  $n_b$ , cover  $n_c$  and thickness  $h$  in a rib area, rib height  $t$  and width  $w$ . A theoretical analysis of rib waveguides was carried out using an effective index method [3].

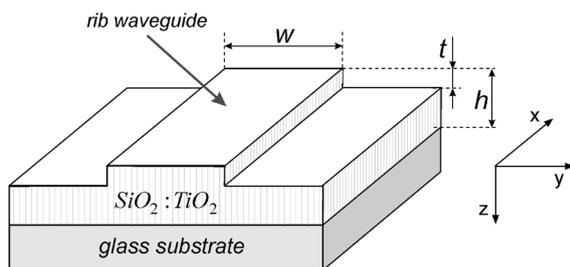


Fig.1 Diagram of a RIB waveguide

Fig.2 shows the calculated modal characteristics of a slab waveguide for TE polarization and a wavelength of  $\lambda=635\text{nm}$ . The values of waveguide refractive indices taken for calculations are: waveguide layer  $n_f=1.793$ , substrate layer  $n_b=1.515$  and cover layer  $n_c=1.000$ . Such

values of refractive indices characterized the structures fabricated in our group.

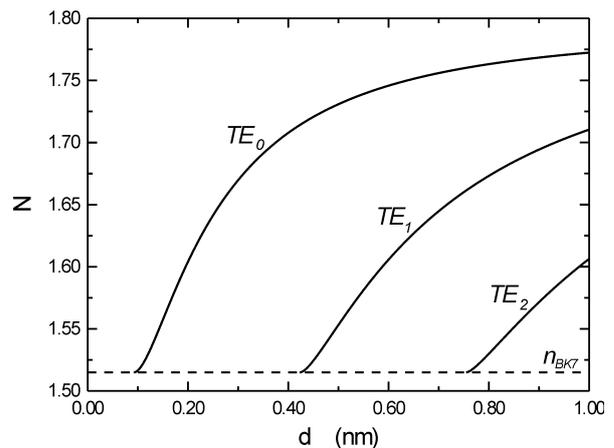


Fig.2 Modal characteristics of a planar waveguide

The modal characteristics of a rib waveguide for selected values of height  $t$  are shown in Fig.3. It can be seen that along with an increase in rib height  $t$  the cut-off width  $w_{cut}$  of  $\text{TE}_{01}$  mode is decreasing. For a rib height of  $t=5\text{nm}$ , the  $\text{TE}_{01}$  cut-off width is  $w_{cut}=2.83\mu\text{m}$ . Silica-titania films were fabricated using a sol-gel method [4]-[6].

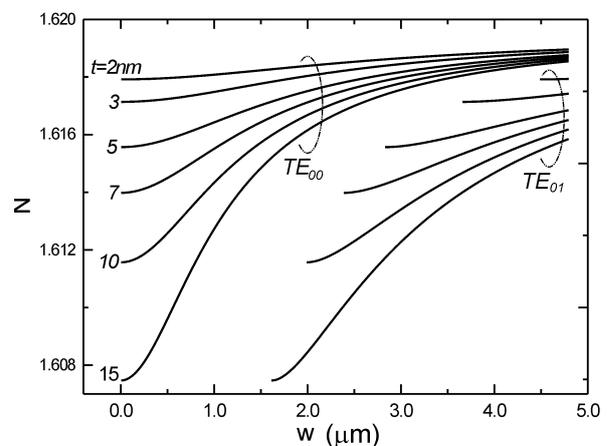


Fig.3 Modal characteristics of a rib waveguide,  $h=219\text{nm}$

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The precursors of silica ( $\text{SiO}_2$ ) and titania ( $\text{TiO}_2$ ) were tetraethyl orthosilicate  $\text{Si}(\text{OC}_2\text{H}_5)_4$  (TEOS) and tetraethyl orthotitanate  $\text{Ti}(\text{OC}_2\text{H}_5)_4$  (TET) respectively. Ethanol  $\text{C}_2\text{H}_5\text{OH}$  was used as a homogenizing agent and hydrochloric acid  $\text{HCl}$  as a catalyst. The TEOS:TET molar ratio of prepared soles was 1. The sol films were deposited on BK-7 glass substrates using a dip-coating method. After depositing sole films on substrates, the structures were annealed for 60 minutes at  $500^\circ\text{C}$ . The thicknesses and refractive indices of fabricated films were measured with a monochromatic ellipsometer Sentech SE400 ( $\lambda=632,8\text{nm}$ ).

Rib waveguides were fabricated by selective etching of silica-titania films. For this purpose a water solution of ammonium fluoride ( $\text{NH}_4\text{F}$ ) was used. The following composition of an etching solution was used: 200ml of water ( $\text{H}_2\text{O}$ ) + 20ml of  $\text{NH}_4\text{F}$  + 10 ml of 80% acetic acid ( $\text{CH}_3\text{COOH}$ ). Our investigations on the composition of etching solutions were carried out on the assumption that the etching speed would be sufficiently low in order to control the etching depth and therefore the rib height, with the etching time. The second obvious demand against an etching solution was its inability to etch a masking layer during the time period, exceeding several times the anticipated etching time. For the etching solution kept at a temperature of  $30^\circ\text{C}$ , the determined etching speed was  $(0.225 \pm 0.003)\text{nm/s}$ . The  $\text{SiO}_2:\text{TiO}_2$  films were masked with a Shipley-Microposit S1813SP15 photoresist. We fabricated rib waveguides of the rib width  $w=1\div 10\mu\text{m}$  and rib-based directional couplers which had the rib width  $w=2\mu\text{m}$ .

The fabricated rib waveguides and directional couplers were investigated using the measurement setup shown in Fig.4. The investigated structures were excited by a laser diode, operating at the wavelength  $\lambda=635\text{nm}$  coupled with a single mode optical fiber. The investigated structure was coupled with an optical fiber through a precise  $x,y,z$  translational stage. The near-field distributions of optical power at the end of excited structures were registered using a CCD camera and stored in a PC computer.

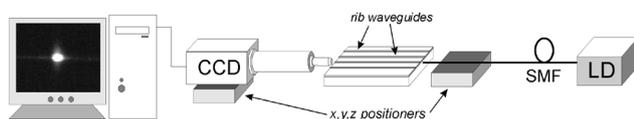


Fig.4 The schematic diagram of measurement setup

Registered optical power distributions at the end of rib waveguides of the rib width  $w=2\div 5\mu\text{m}$  are shown in Fig.5. All investigated rib waveguides had the same rib height  $t=5\text{nm}$ .

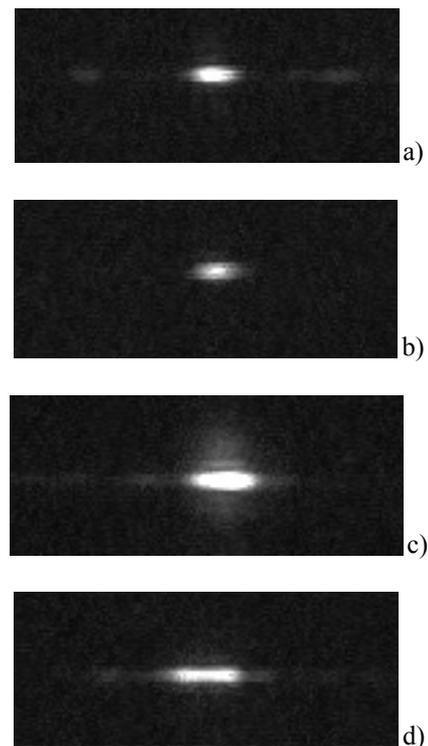


Fig.5 Registered optical power distributions at the end of rib waveguides for ribs of different width: a)  $w=2\mu\text{m}$ , b)  $w=3\mu\text{m}$ , c)  $w=4\mu\text{m}$ , d)  $w=5\mu\text{m}$ .

The analysis of registered optical power distributions showed that rib waveguides of the rib width  $w=2\mu\text{m}$  and  $w=3\mu\text{m}$  are single mode, whereas those for the rib of a width greater than  $3\mu\text{m}$  are multimode for the wavelength  $\lambda=635\text{nm}$ . The determined attenuation of fabricated rib waveguides is approximately  $1.5\text{dB/cm}$ . The attenuation was measured using a streak method. At the current stage of investigations, sidewall roughness is the main source of attenuation. This roughness results from copying, in a photolithographic process, the defects the photolithographic mask is burden with. The photolithographic mask used in a rib fabrication processes is negative.

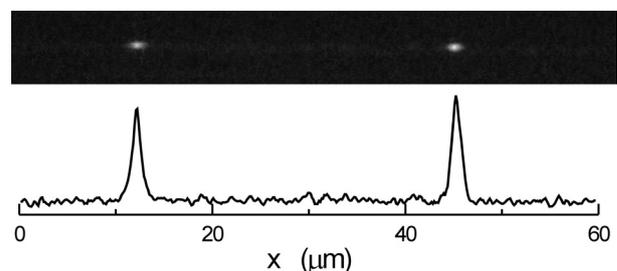


Fig.6 Near-field picture of a 1x2 directional coupler outgoing rib waveguides and related distribution of optical power

The registered near-field picture of a 1×2 directional coupler outgoing rib waveguides is shown in Fig.6. In this figure is also shown optical power distribution determined on the basis of this picture. It can be seen that the values of optical power in both rib waveguides are very close to one another.

The presented rib waveguides and directional couplers may be the basis for developing planar interferometers for sensor applications. We expect that improvement in the quality of a photolithographic mask as well as the optimization of an etching process will allow us to fabricate structures characterized by lower attenuation.

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